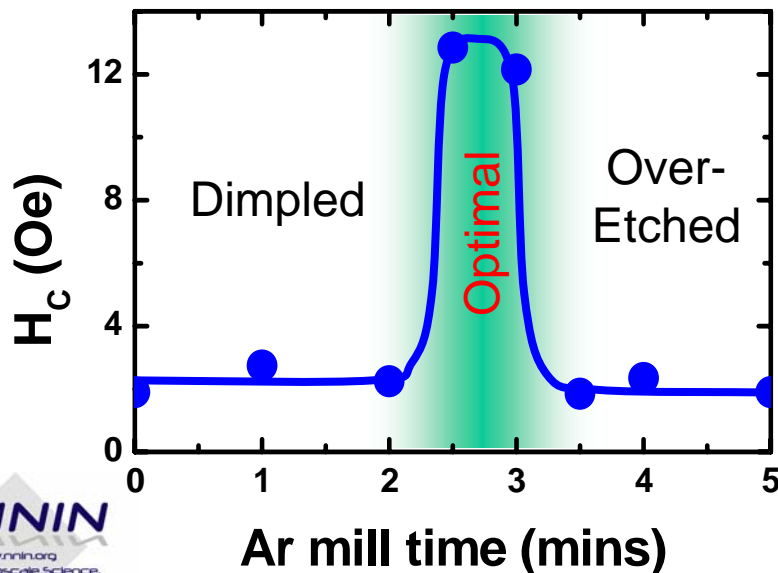
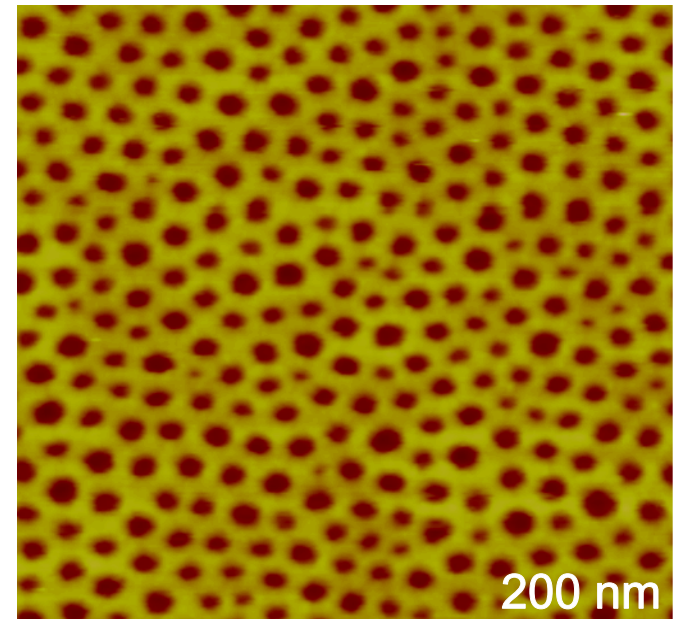


Large Area Magnetic Antidot Array Fabrication Via Block Copolymer Lithography

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- Spin coat cylinder forming PS-PI-PLA triblock copolymer to use as pattern template.
- Anneal to orient the PLA cylinders.
- Degrade PLA component in NaOH solution then transfer pattern to NiFe film via Ar ion milling.



- Pattern transfer process characterized by AFM, magnetometry, and magneto-transport.
- Magnetometry allows accurate determination of optimal milling time.